

# PHI VersaProbe II Scanning XPS Microprobe



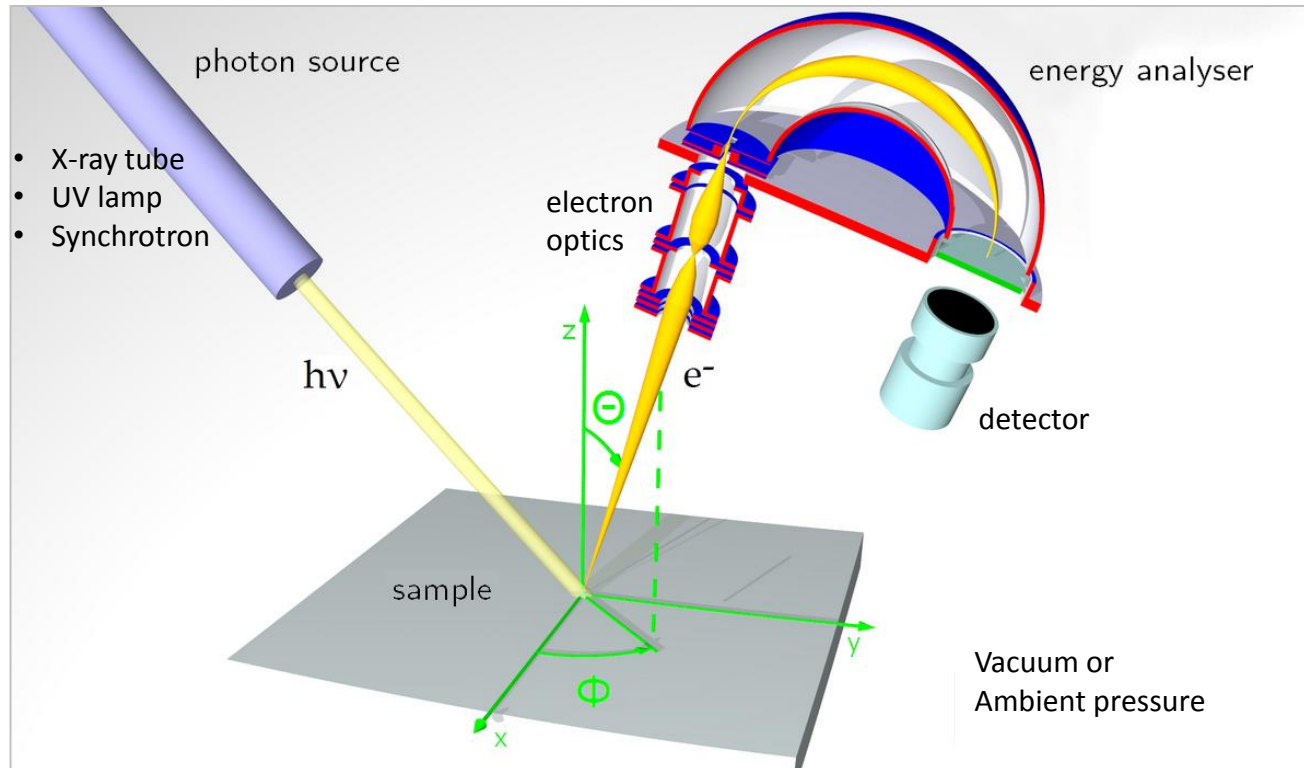
# Core Policies

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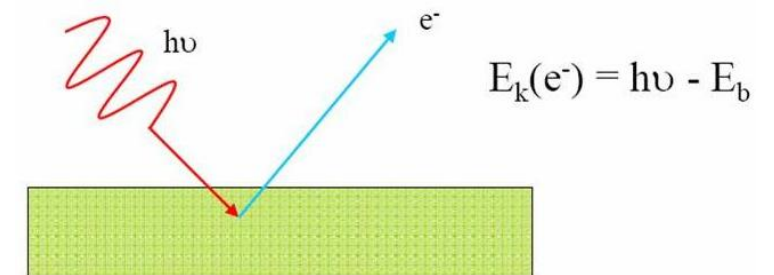
- **DO NOT** let other people use the facility under your account.
- **DO NOT** try to fix parts or software issues by yourself!
- **DO NOT** surf web using instrument computer!
- **Follow** [checklist](#) and [SOP](#)! **DO NOT** explore program!
  
- **Facility usage time** at least twice a month, **OR** receive training again ([two practice sessions](#) within one week).
- **No trainings** on monthly users

# What is XPS? X-ray Photoelectron Spectroscopy

- Photoelectric effect
- A spectroscopy that records the counts of X-ray induced secondary electrons - photoelectrons as the function of binding energy

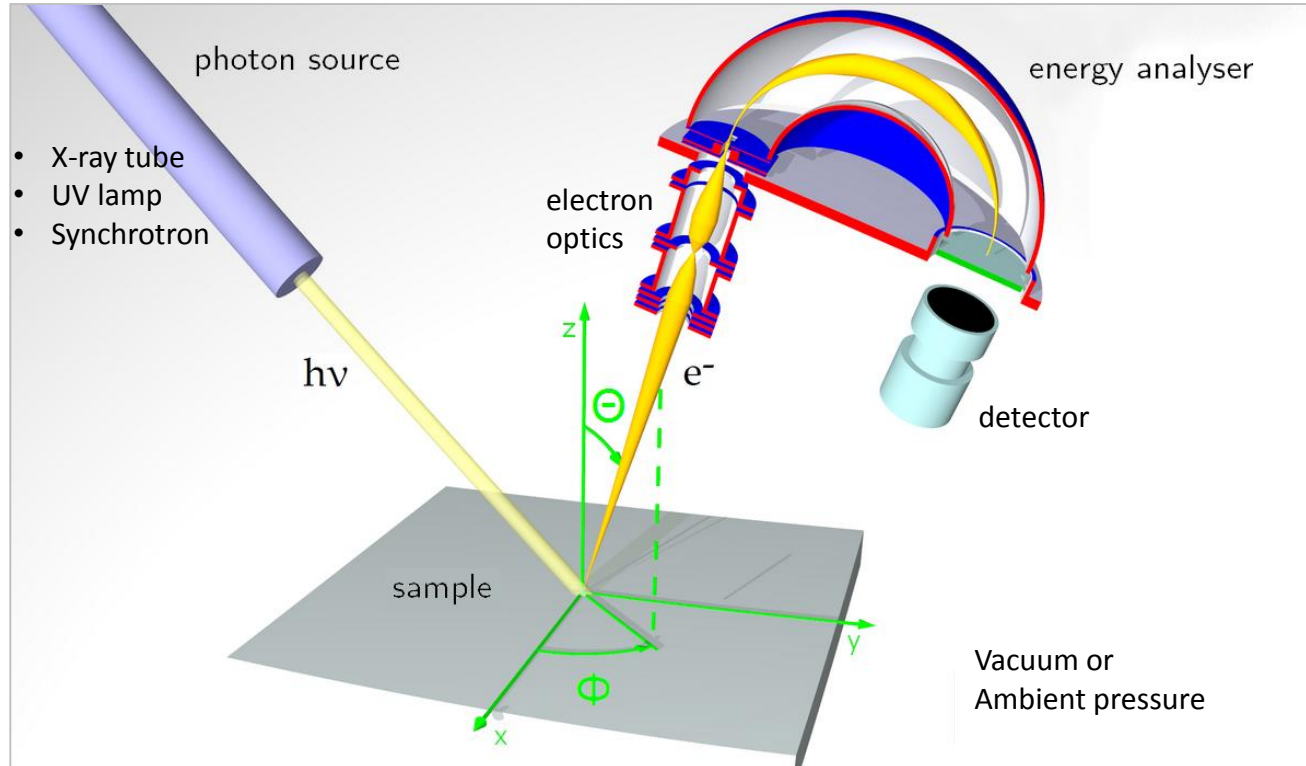


- A technique based on photoelectric effect:

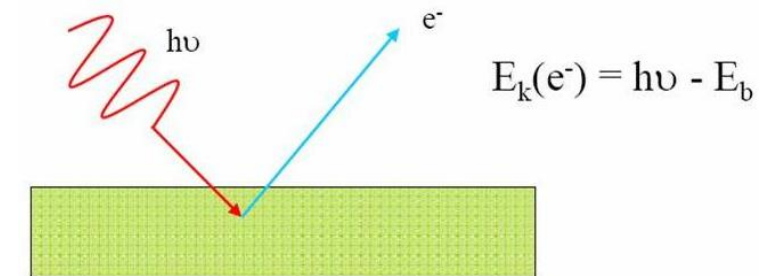


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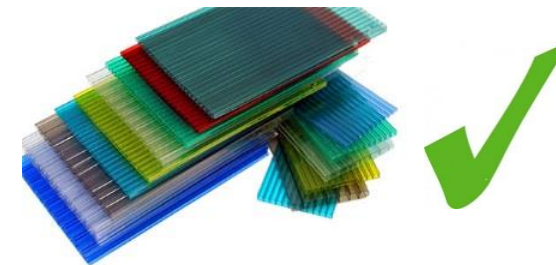
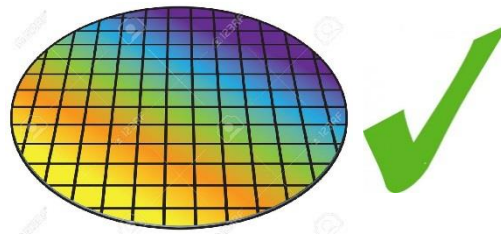
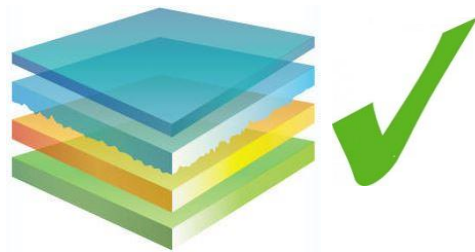


# What kinds of samples for XPS?

- Vacuum compatible: low vapor pressure under  $10^{-8}$  Pascal
- Conductive or insulating



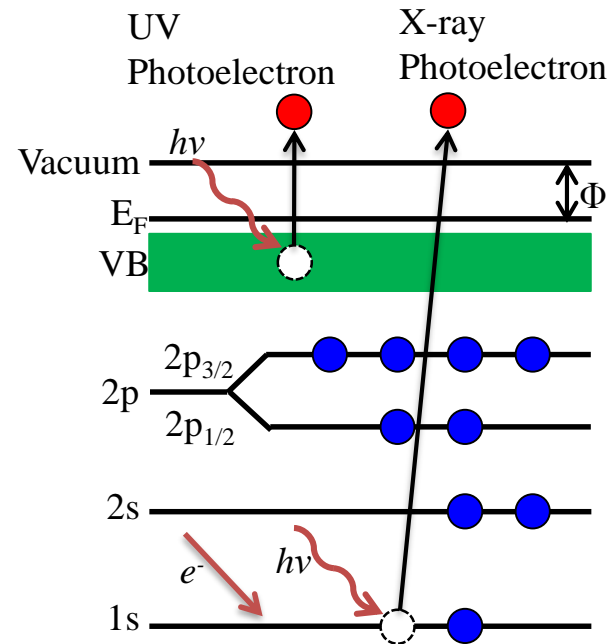
Freezing



# How XPS works?

- XPS detects the number of photoelectrons at different kinetic energies (KE)
- The photoelectron binding energy can then be calculated, characteristic of elements within the sample volume

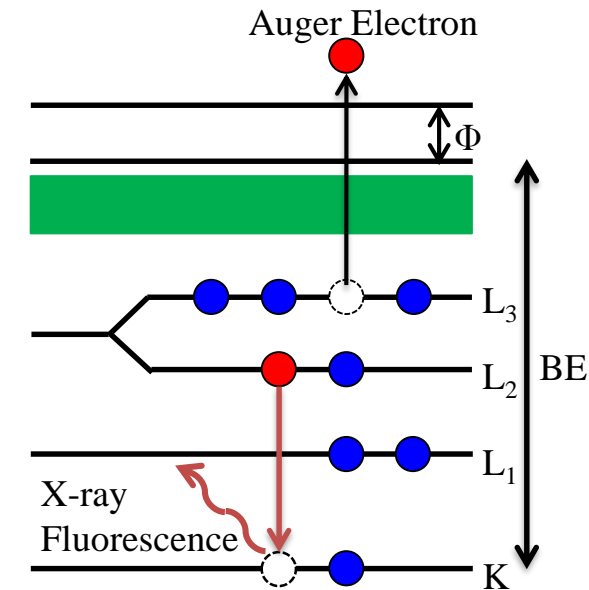
Ionization (initial state)



$$KE \text{ (measured)} = h\nu - BE - \Phi_{\text{spec}}$$

$$BE = h\nu - KE - \Phi_{\text{spec}}$$

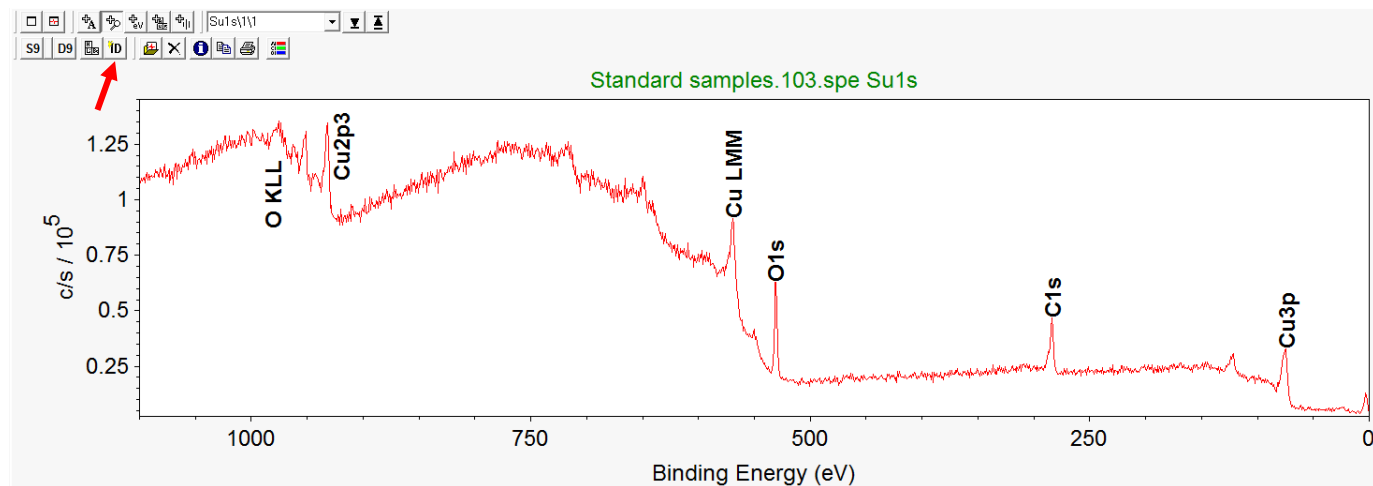
Relaxation and Emission (final state)



$$KE \text{ (KLL)} = BE(K) - BE(L_2) - BE(L_3)$$

# XPS Main Features

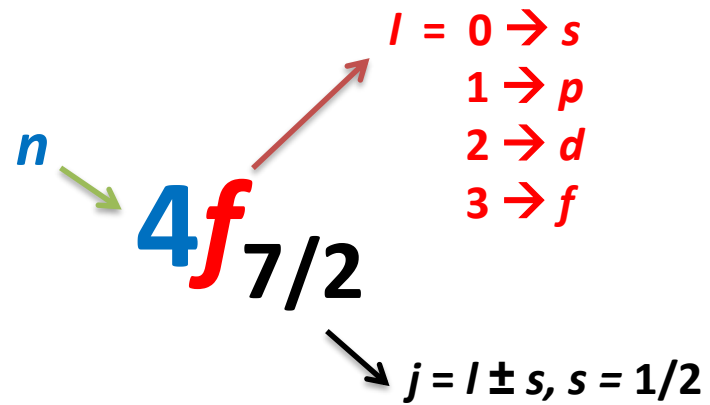
- Core level splitting
- Auger peaks
- Stepped background ← inelastic secondary electrons



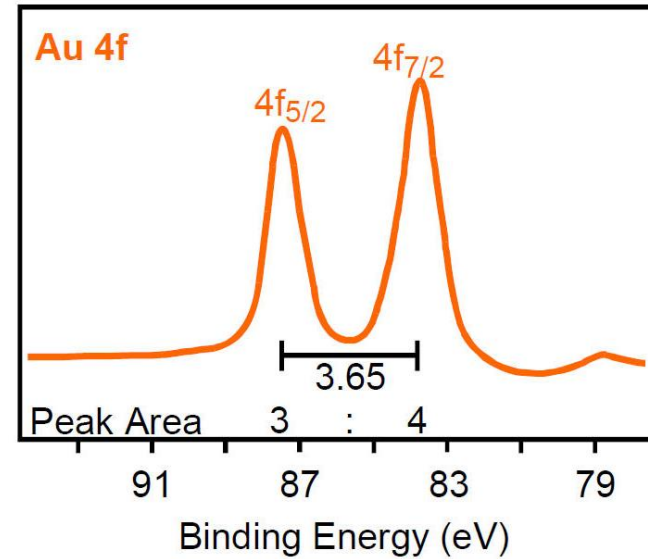
KE →

← BE

# XPS Peak Notation

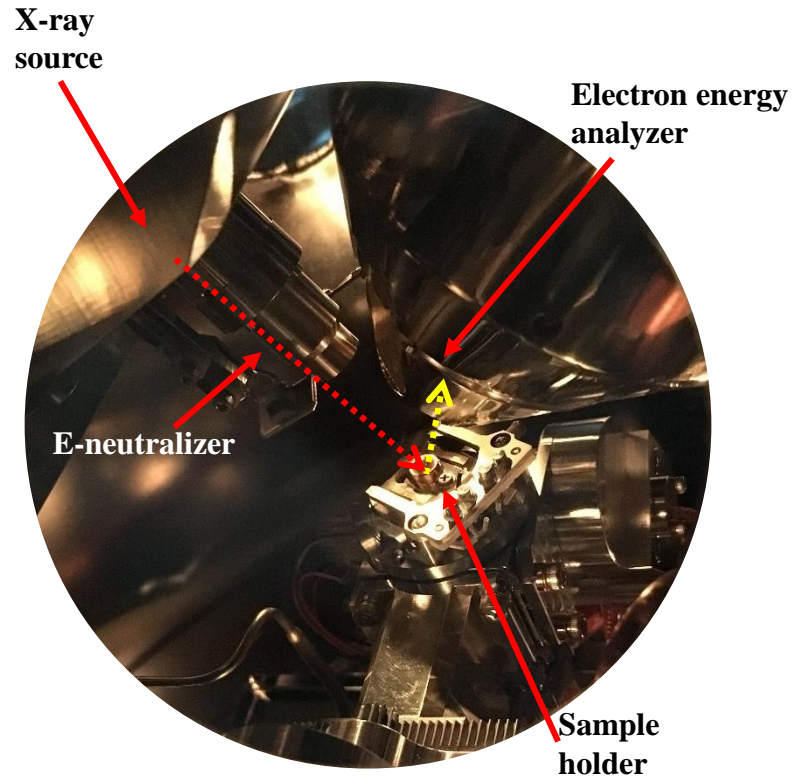
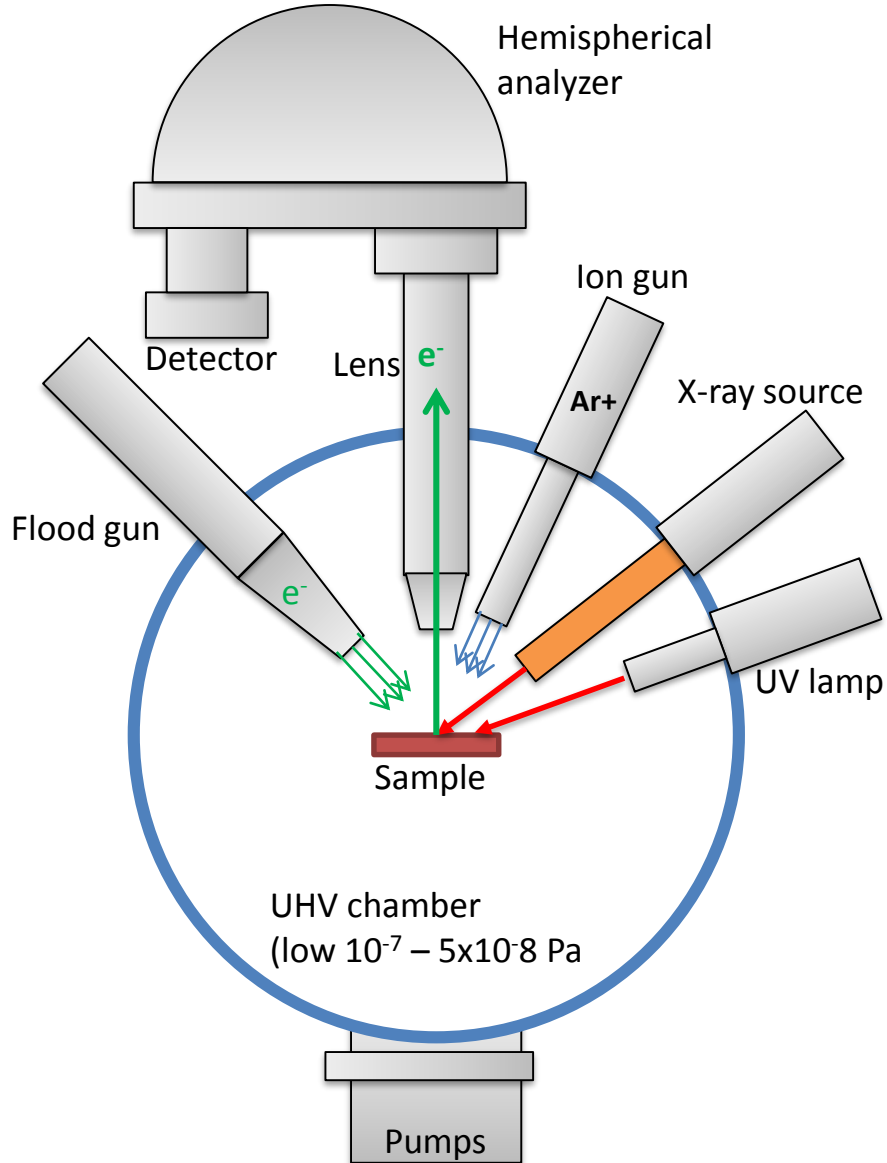


Spin-orbital splitting with  $l > 0$



| Orbital | $l$ | $j$      | Degeneracy ( $2j + 1$ ) | Peak area ratio | Electron level       |
|---------|-----|----------|-------------------------|-----------------|----------------------|
| s       | 0   | 1/2      | 1                       | -               | 1s                   |
| p       | 1   | 1/2, 3/2 | 2, 4                    | 1 : 2           | $2p_{1/2}, 2p_{3/2}$ |
| d       | 2   | 3/2, 5/2 | 4, 6                    | 2 : 3           | $3d_{3/2}, 3d_{5/2}$ |
| f       | 3   | 5/2, 7/2 | 6, 8                    | 3 : 4           | $4f_{5/2}, 4f_{7/2}$ |

# XPS Instrumentation



PHI VersaProbe II XPS

UHV system ( $< 10^{-8}$  Torr)

- Surface clean
- Longer photoelectron path length

Electron analyzer

- Lens to collect photoelectrons
- Analyzer to filter electron energies
- Detector to count electrons

X-ray source

- Al  $K\alpha$  1486.6 eV; Mg  $K\alpha$  1256.6 eV
- Monochromated using quartz crystal

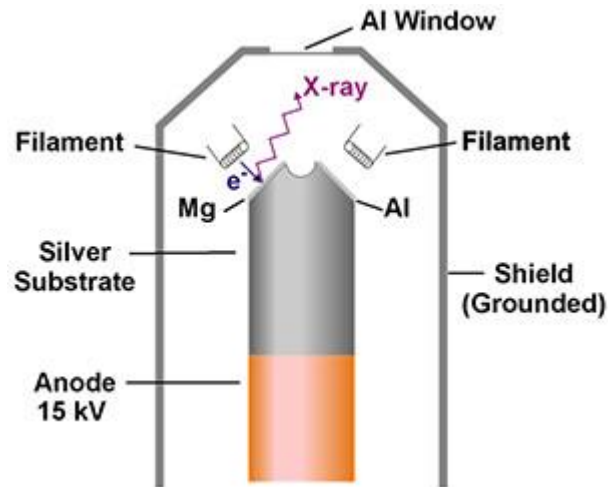
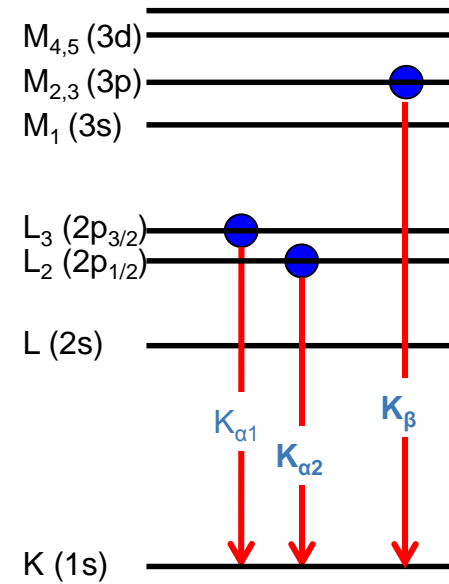
Low-energy electron flood gun

- Insulating samples

Ion gun

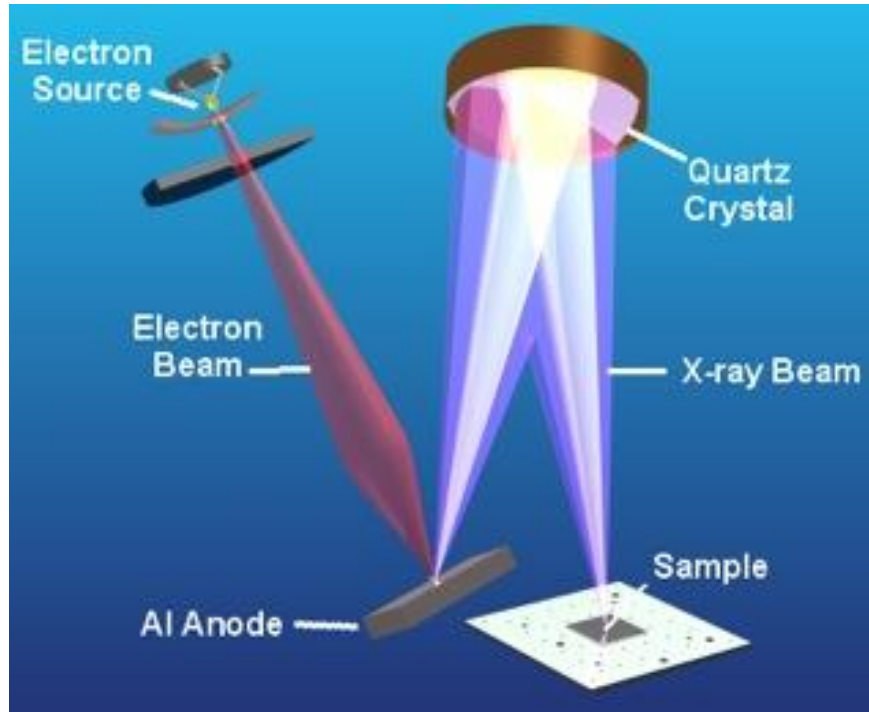
- Sample cleaning
- Depth profiling
- For polymers, cluster ion sources may be required

# X-ray Dual Anode Source



| X-ray lines          | Line Energy (eV) | Width (eV) |
|----------------------|------------------|------------|
| Mg K <sub>α1,2</sub> | 1253.6           | 0.70       |
| Al K <sub>α1,2</sub> | 1486.6           | 0.85       |

# X-ray monochromator



- Narrow peak width
- Reduced background
- No satellite & Ghost peaks

$$n \lambda = 2d \sin \theta$$

For quartz ( $10\bar{1}0$ ) surface:

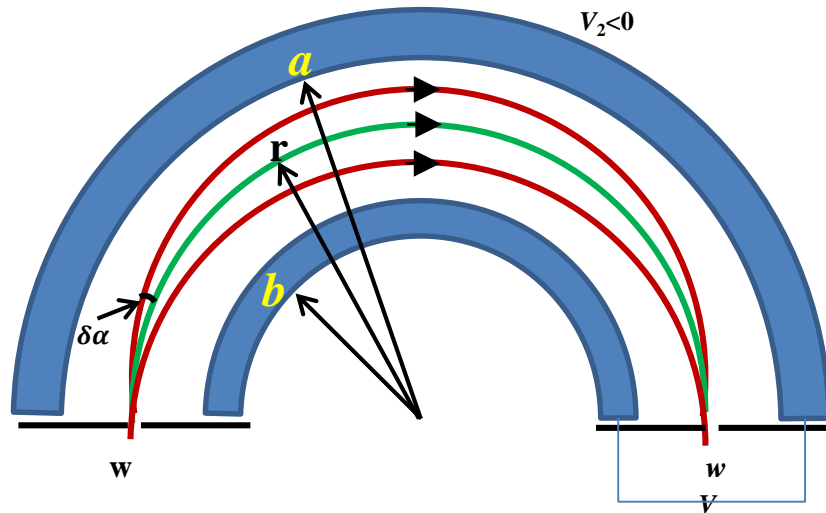
$n$  = diffraction order

$d$  = 0.42 nm (lattice constant)

$\theta$  =  $78.5^\circ$

$\lambda$  = 0.83 nm for Al  $K\alpha$

# Spherical Capacitor Analyzer (SCA)



Pass energy:

$$E_0 = eV_0 = \frac{V}{\left(\frac{b}{a} - \frac{a}{b}\right)}$$

Analyzer Resolution:

$$\Delta E = E_0 \left( \frac{w}{a+b} + \frac{\delta\alpha^2}{4} \right)$$

Where the mean radius

$$r = \frac{a+b}{2}$$

$V_0$ : the median equipotential surface of radius  $r$

$V$ : the potential applied between inner (radius  $b$ ) and outer (radius  $a$ ) shells

$w$ : entrance and exit slit widths

$\delta\alpha$ : angular deviation of the electron trajectories at the entrance with respect to the center line

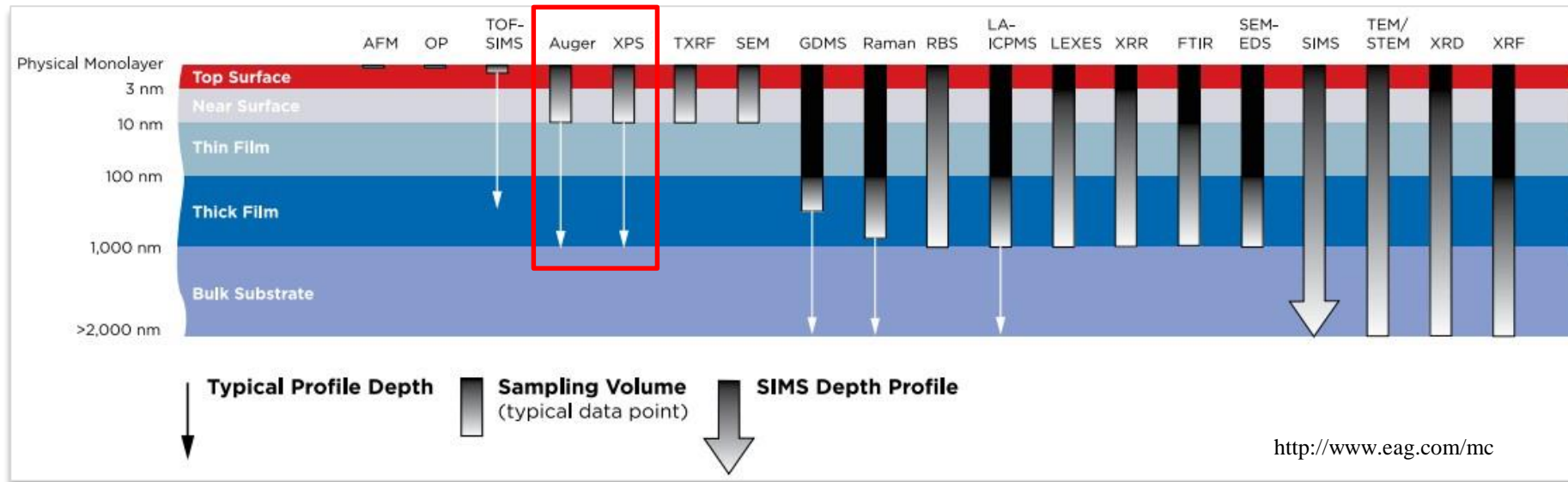
For the PHI SCA :  $E_0 = 0.56V$  and  $\Delta E = 0.015E_0$

Typical  $E_0 = 100 \text{ eV}$   $\rightarrow \Delta E = 1.5 \text{ eV}$

# Why are we interested in XPS?

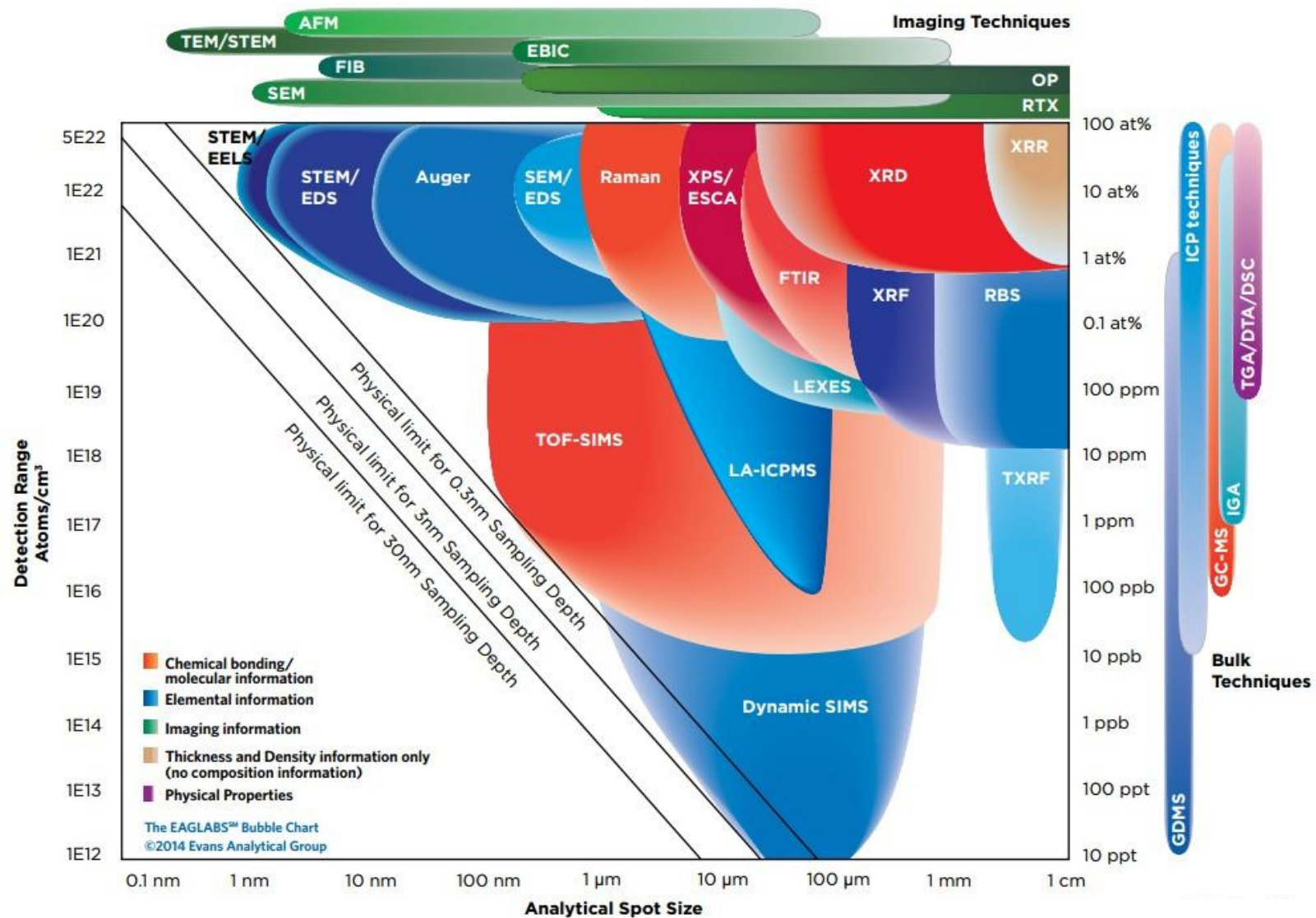
- Surface sensitive technique
- Chemical shift detection → XPS is also named as Electron Spectroscopy for Chemical Analysis (ESCA)

## Typical Analysis Depths for Techniques



XPS detects electron signals in the near surface region (0 ~ 10 nm)

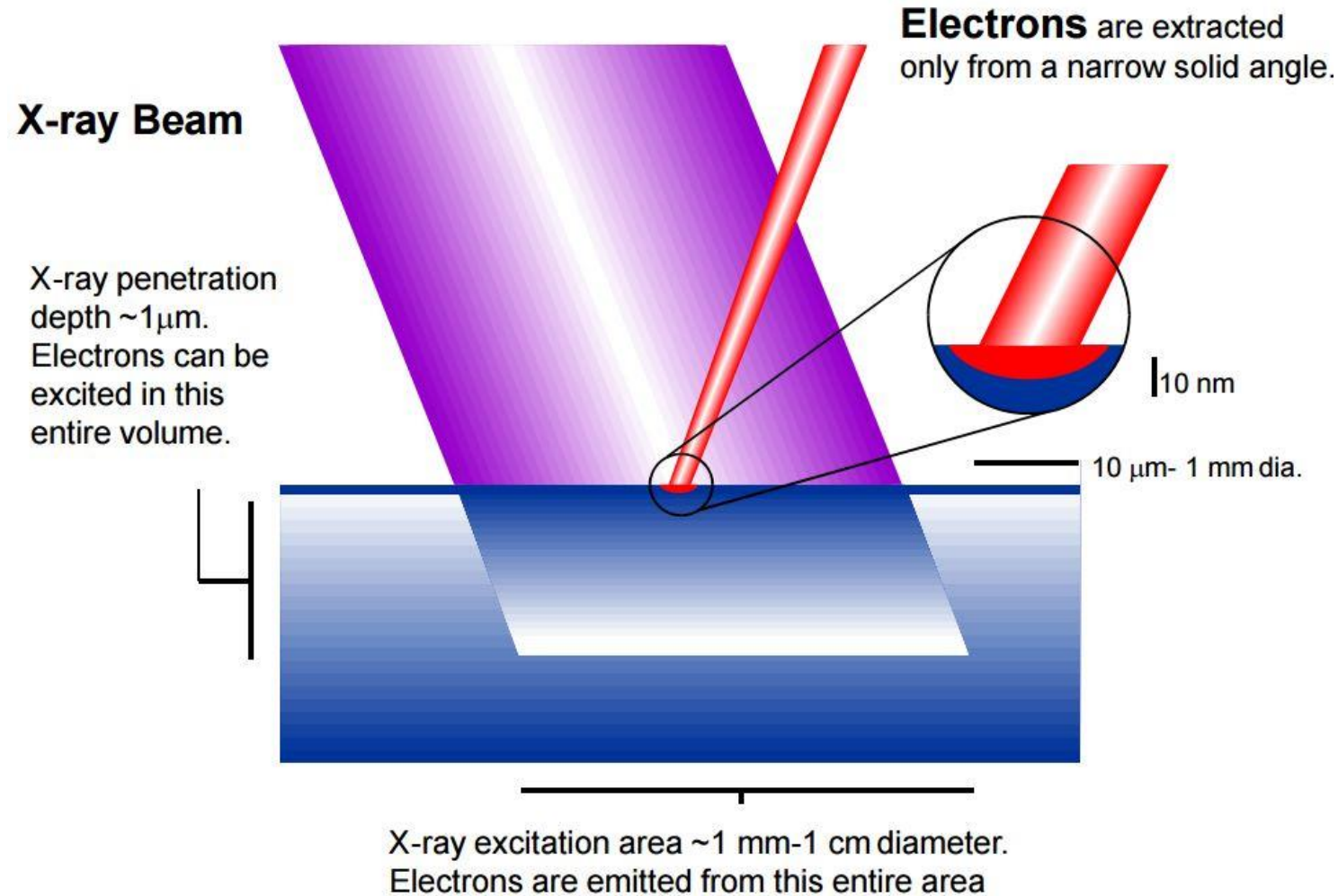
# Analytical Resolution vs. Detection Limit



- XPS resolution can be reached below 10  $\mu\text{m}$
- XPS detection limits: ppt range

# Why XPS is Surface Sensitive?

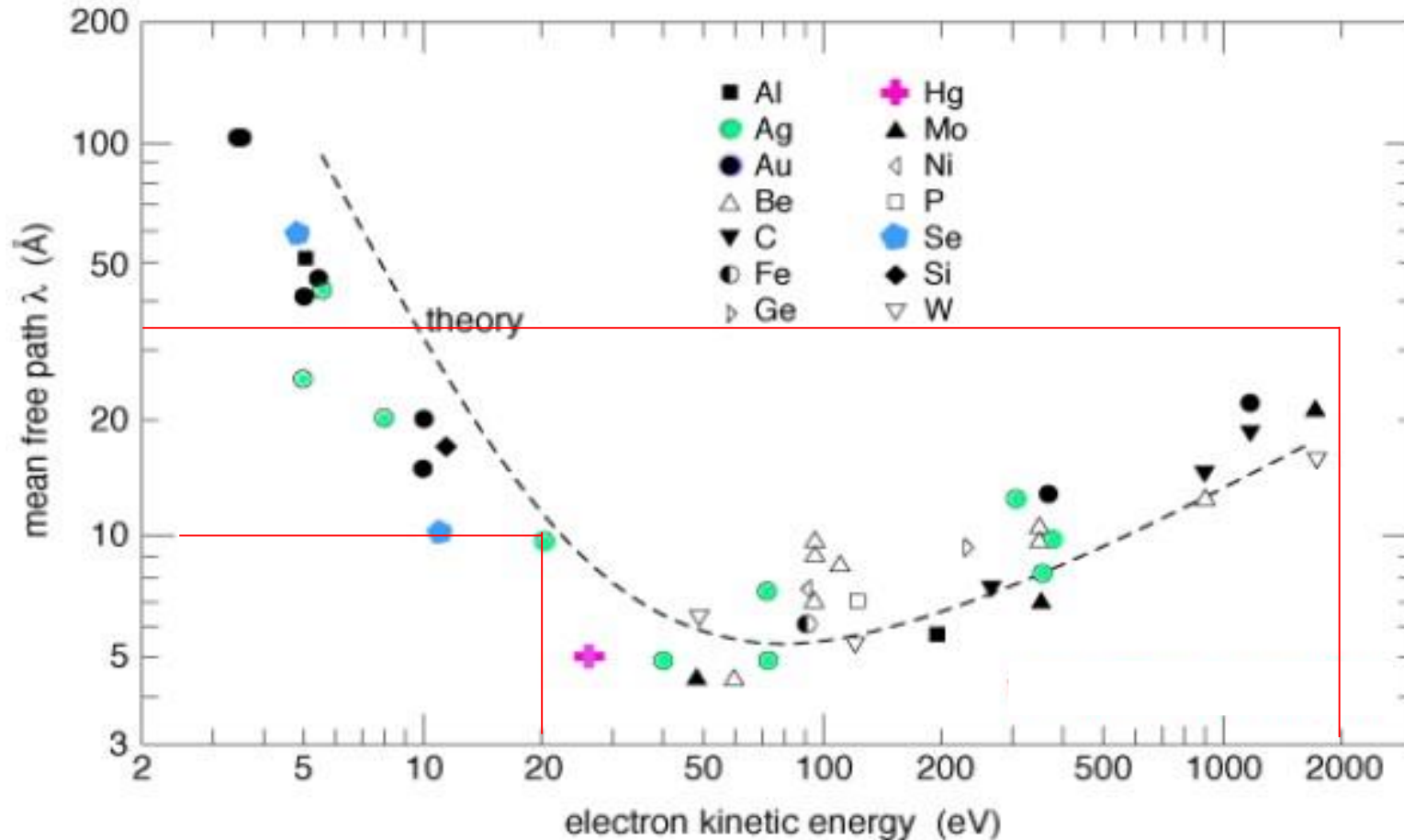
- Inelastic scattering of photoelectrons



# Electron Inelastic Mean Free Path (IMFP)

- The average distance an electron travels through a solid before losing energy through inelastic collisions.

“Universal Curve” -  $\lambda$  (IMFP) vs kinetic



$\lambda = 1 \sim 3.5$  nm for X-ray photoelectrons